

Claims

1. A chemical amplifying type positive resist composition comprising

a resin which has a polymerization unit derived from

5 hydroxystyrene and a polymerization unit derived from 2-ethyl-2-adamantyl (meth)acrylate, and is insoluble or poorly soluble itself in an alkali, but becomes alkali-soluble after dissociation of the above-mentioned acid unstable group by the action of an acid;

10 a radiation sensitive acid generating agent; and polypropylene glycol.

2. The chemical amplifying type positive resist composition according to claim 1, wherein content of the propylene glycol is from 0.1 to 5% by weight of the total solid
15 content in the resist.

3. The chemical amplifying type positive resist composition according to claim 1, wherein weight-average molecular weight of the polypropylene glycol is from 500 to 5000.

20 4. The chemical amplifying type positive resist composition according to claim 1, wherein the radiation sensitive acid generating agent contains at least one compound selected from the group consisting of onium salt compounds, organo-halogen compound, sulfone compounds, sulfonate
25 compounds, and the like.